

Notice of References Cited	Application/Control No. 10/707,707	Applicant(s)/Patent Under Reexamination LEE ET AL.	
	Examiner Toniae M. Thomas	Art Unit 2822	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-2003/0032224 A1	02-2003	Sung et al.	438/197
	B	US-2004/0094793 A1	05-2004	Noguchi et al.	257/315
	C	US-5,910,453	06-1999	Gupta et al.	438/717
	D	US-6,674,132 B2	01-2004	Willer, Josef	257/390
	E	US-6,743,681 B2	06-2004	Bhattacharyya, Arup	438/287
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Wolf, Ph.D., Stanley, Richard N. Tauber, Ph.D., "Chemical Vapo Deposition of Amorphous and Polycrystalline Films," Silicon Processing for the VLSI Era - Vol. 1: Process Technology, Lattice Press, 1986, pp. 183-185.
	V	Wolf, Ph.D., Stanley, Richard N. Tauber, Ph.D., "Thermal Oxidation of Single Crystal Silicon," Silicon Processing for the VLSI Era - Vol. 1: Process Technology, Lattice Press, 1986, p. 198.
	W	Wolf, Ph.D., Stanley, Richard N. Tauber, Ph.D., "Lithography I: Optical Resist Materials and Process Technology," Silicon Processing for the VLSI Era - Vol. 1: Process Technology, Lattice Press, 1986, p. 438.
	X	Wolf, Ph.D., Stanley, "Multilevel-Interconnect Technology for VLSI and ULSI," Silicon Processing for the VLSI Era - Vol. 2: Process Integration, Lattice Press, 1990, pp. 273.

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.